

The invention relates to a multi-mirror-system for an illumination system, especially for lithography with wavelengths ≤ 193 nm comprising an imaging system, wherein said imaging system comprises at least a first mirror and a second mirror, an object plane, an image plane, wherein the imaging system forms an image of the object, an arc-shaped field in said image plane, whereby the radial direction of in the middle the arc-shaped field defines a scanning direction. The multi-mirror-system is characterized in that at least said first mirror and said second mirror of said imaging system are arranged in the optical path of the imaging system in such a position and having such a shape, that the edge sharpness of the arc-shaped field in the image plane is smaller than 5 mm, preferably 2 mm, most preferably 1 mm in scanning direction.

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